

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:	
Kwanyoung LEE, Young Jin KIM and Jong-geun KIM	Examiner: Unknown
Serial No.: Unknown	Art Unit: Unknown
Filed: July 22, 2003	
For: TERNARY BLOCK COPOLYMER AND MANUFACTURING METHOD OF THE SAME	

Mail Stop Patent Application
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT

Sir or Madam:

Please amend the application as follows:

IN THE SPECIFICATION:

Please insert the following paragraph at page 1, line 3:

PRIORITY REFERENCE TO PRIOR APPLICATION

This application claims benefit under 35 U.S.C. §119 of Korean patent application number 10-2002-0061654, entitled "Ternary Block Copolymer and Manufacturing Method of the Same," filed on October 10, 2002, by inventors Kwanyoung Lee, Young Jin Kim and Jong-geun Kim.